

**PATENT**

**IN THE UNITED STATES PATENT OFFICE**

In re application of:  
Zhiping Yin  
Gurtej S. Sandhu

Serial No.: Not Assigned

Filed: September 24, 2003 (Concurrently Herewith)

For: **ANTIREFLECTIVE COATING FOR USE  
DURING THE MANUFACTURE OF A  
SEMICONDUCTOR DEVICE**

§  
§ Group Art Unit: Not Assigned  
§  
§ Examiner: Not Assigned  
§  
§ Atty. Docket: 2003-0790.00/US  
§  
§ Paper No. \*  
§  
§

Mail Stop Patent Application  
Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

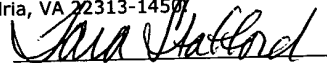
Dear Sir:

**Certificate of Express Mailing (37 CFR §1.10)**

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Date of Deposit: September 24, 2003

I hereby certify that this paper is being deposited with the United States Postal Service "Express Mail Post Office to Addressee" service under 37 CFR §1.10 on the date indicated above and is addressed to the Commissioner for Patents, PO Box 1450, Alexandria, VA 22313-1450.

  
Signature

**INFORMATION DISCLOSURE STATEMENT**

In compliance with the duty of disclosure under 37 CFR §1.56, Applicant respectfully requests entry of this Information Disclosure Statement, and that the references listed on the attached Form PTO-1449 be considered by the Examiner and made of record. As the references consist only of patent documents cumulative from the parent, copies are not enclosed.

In accordance with 37 CFR §1.97(b), this Information Disclosure Statement is not to be construed as a representation that a search has been made or that no other possible material information as defined in 37 CFR §1.56(a) exists.

The following reference is submitted for the Examiner's review:

**U.S. Patent Documents**

<b>Document No.</b>	<b>Date</b>	<b>Inventor</b>
4,675,265	06/1987	Kazama et al.
6,333,255	12/2001	Sekiguchi
6,469,425	10/2002	Sakai et al.
US-2002-0088707	07/2002	Towle

**Other References:**

Copending Application: "Boron-Doped Amorphous Carbon Film For Use as a Hard Etch Mask During the Formation of a Semiconductor Device", Serial number 10/463,185, Docket Number 2002-0858.00/US, Filed June 17, 2003.

As this Information Disclosure Statement is being submitted before the mailing of a first Office Action on the merits, no fee is due. However, the Commissioner is authorized to charge any required fee to Micron Technology Inc. Deposit Account No.13-3092, Order No. 2003-0790.00/US.

If there are any matters which may be resolved or clarified through telephone interview, the Examiner is respectfully requested to contact Applicant's undersigned agent at the number indicated.

\* \* \* \*

A Form PTO-1449 is enclosed herewith.

Respectfully submitted,



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FORM: PTO-1449 (REV: 7-80)	U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE	Atty Docket No: <b>2003-0790.00/US</b>	Serial No: <b>Not Assigned</b>
<b>INFORMATION DISCLOSURE STATEMENT BY APPLICANT</b>  (37 CFR 1.98(b)) (use several sheets if necessary)		Applicant: <b>Micron Technology, Inc.</b>	
		Filing Date: <b>September 24, 2003</b>	Group: <b>Not Assigned</b>

**U.S. PATENT DOCUMENTS**

Examiner Initial	Document Number	Date	Name	Class	Subclass	
	AA	4,675,265	06/1987	Kazama et al.	430	67
	AB	6,333,255	12/2001	Sekiguchi	438	622
	AC	6,469,425	10/2002	Sakai et al.	313	310
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	AE					
	AF					
	AG					
	AH					
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	AJ					
	AK					

**FOREIGN PATENT DOCUMENTS**

Examiner Initial	Document Number	Date	Country	Class	Subclass	Translation Yes	No
	AL					<input type="checkbox"/>	<input type="checkbox"/>
	AM					<input type="checkbox"/>	<input type="checkbox"/>
	AN					<input type="checkbox"/>	<input type="checkbox"/>

**OTHER ART** (including author, title, date, pertinent pages, etc.)

Initial		
	AO	Copending Application: "Boron-Doped Amorphous Carbon Film For Use as a Hard Etch Mask During the Formation of a Semiconductor Device", Serial number 10/463,185, Docket Number 2002-0858.00/US, Filed June 17, 2003.
	AP	
	AQ	
	AR	

Examiner:	Date Considered:
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EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication with applicant.

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